



**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q81014

Shuho MOTOMURA

Appln. No.: 10/820,791

Group Art Unit: 1762

Confirmation No.: 8726

Examiner: Katherine A. BAREFORD

Filed: April 9, 2004

For: RESIST FILM FORMING METHOD AND A PHOTOMASK MANUFACTURING  
METHOD

**AMENDMENT UNDER 37 C.F.R. § 1.111**

**MAIL STOP AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated June 8, 2006, please amend the above-identified application as follows on the accompanying pages.

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